

Tool Code	PROCESS	EQUIPMENT	MANUFACTURER	MODEL	WAFER SIZE	VINTAGE
7744	TEST	WAFER PROBER	ACCRETECH	UF200	200	2000
7615	TEST	WAFER PROBER	ACCRETECH	UF200	200	-
7824	TEST	WAFER PROBER	ACCRETECH	UF200	200	1998
7756	TEST	WAFER PROBER	ACCRETECH	UF200A	200	2003
7764	TEST	WAFER PROBER	ACCRETECH	UF200SA	200	2005
7765	TEST	WAFER PROBER	ACCRETECH	UF200SA	200	2005
7766	TEST	WAFER PROBER	ACCRETECH	UF200SA	200	2004
7779	TEST	WAFER PROBER	ACCRETECH	UF3000	300	2006
7739	TEST	WAFER PROBER	ACCRETECH	UF3000EX	300	2014
7373	TEST	TESTER	ADVANTEST (Verigy)	93000 C200e	300	2007
7655	TEST	TESTER	Agilent	4072A	150	2004
7693	TEST	TESTER	Agilent	4073A	300	2002
8409	TEST	TESTER_PARAMETRIC TEST	Agilent	4142B	150	2000
7782	CVD	CVD	Applied Materials	AKT-3500	-	2018
7201	ETCH	POLY ETCHER	Applied Materials	Centura DPS	200	1998
7320	CVD	PLASMA CVD	Applied Materials	Centura DXZ	150	1999
7204	ETCH	OXIDE ETCHER	Applied Materials	Centura MXP	200	1997
8290	RTP	RTA	Applied Materials	Centura XE	200	2003
7859	RTP	RTA	Applied Materials	Centura XE+	200	2003
8411	CVD	PLASMA CVD	Applied Materials	P-5000	150	1990
7424	CVD	PLASMA CVD	ASM	Eagle10	200	1998
7104	CVD	PLASMA CVD	ASM	Eagle10 TRIDENT	150	2007
7617	CVD	AP-CVD	Aviza	WJ-1000H	200	1996
8261	RTP	RTA	Canon	HP-8800	200	2001
7719	ETCH	ASHER	Canon	MAS-8200	200	-
7466	ETCH	ASHER	Canon	MAS-8220	200	-
7849	PHOTOLITHO	MASK ALIGNER	Canon	MPA-600FA	150	1988
7677	PVD	SPUTTERING SYSTEM	CANON ANELVA	I-1060SV2 Plus1	200	1999
7819	PVD	SPUTTERING SYSTEM	CANON ANELVA	I-1080PVD	200	2001
8273	PVD	SPUTTERING SYSTEM	CANON ANELVA	ILC-1080	200	2003
7428	OTHERS	VACUUM LEAK DETECTOR	CANON ANELVA	M-222LD-D	-	2011
7641	DICING	DICER	DISCO	DAD3350	200	-
7642	DICING	AUTOMATIC CLEANING SYSTEM	DISCO	DCS141	200	-
7640	DICING	DICER	DISCO	DFD-2S/8	200	-
7837	DICING	DICER	DISCO	DFD6240	200	2004
7486	DICING	DICER	DISCO	DFD6340	200	2008
7290	OTHERS	GAS SCRUBBER	EBARA	GDC250SA	200	2012
7487	PLATING	PLATING	EBARA	UFP100(150A)	200	-
7089	TEST	LASER REPAIR SYSTEM	ESI	ESI 9350	200	2004
8392	METROLOGY	FILM STRESS MEASURMENT	FSM	FSM-128	200	2001
8134	METROLOGY	FILM STRESS MEASURMENT	FSM	FSM-128	200	-
7653	MARKING	Wafer Marker	GSI	MARK-EM	150	2002
7517	ETCH	ION MILLING	HITACHI	IML-6-1	150	1997
8163	OTHERS	AIR DUST MONITOR	HITACHI	TS-3700	200	1990
8283	OTHERS	AIR DUST MONITOR	HITACHI	TS-6500	200	2000
7733	METROLOGY	FIB	Hitachi High-Tech	FB-2100	-	2002
7749	ETCH	ION MILLING	Hitachi High-Tech	IM4000	-	2012
7768	METROLOGY	NANO PROBER	Hitachi High-Tech	NE4000	-	2011

Tool Code	PROCESS	EQUIPMENT	MANUFACTURER	MODEL	WAFER SIZE	VINTAGE
7852	METROLOGY	REVIEW SEM	Hitachi High-Tech	S-3400N	-	2010
7748	METROLOGY	REVIEW SEM	Hitachi High-Tech	S-3700N	-	2012
7780	METROLOGY	REVIEW SEM	Hitachi High-Tech	S-4500	-	1996
7406	METROLOGY	REVIEW SEM	Hitachi High-Tech	S-4800	-	2004
7758	METROLOGY	MICROSCOPE	Hitachi High-Tech	TM3000	-	2012
7563	MARKING	LASER MARKER	KEYENCE	ML-Z9500/9510	-	2008
7868	METROLOGY	DEFECT INSPECTION	KLA/TENCOR	AIT II	200	1999
7723	METROLOGY	OVERLAY METROLOGY SYSTEM	KLA-Tencor	ARCHER200	300	2009
7594	METROLOGY	REVIEW SEM	KLA-Tencor	eDR5210S	300	2011
7857	METROLOGY	FILM THICKNESS MEASUREMENT	KLA-Tencor	UV1280SE	200	2003
8451	METROLOGY	LIFETIME MEASURING	KOBELCO	LTA-500	150	1996
7220	METROLOGY	LIFETIME MEASURING	KOBELCO	LTA-550	200	1991
7669	BONDING	WIRE BONDER	Kulicke & Soffa	Maxum ultra	-	2008
7670	BONDING	WIRE BONDER	Kulicke & Soffa	Maxum ultra	-	2008
6953	CVD	PLASMA CVD_W	Lam Research	CONCEPT ONE-W	150	1995
7850	CVD	PLASMA CVD	Lam Research	CONCEPT TWO	150	2000
7235	CVD	PLASMA CVD	Lam Research	CONCEPT TWO Speed	200	2000
7179	WET	SPIN ETCHER	Lam Research	RST201	200	1996
7240	WET	SPIN ETCHER	Lam Research	RST201	200	1997
7734	WET	SPIN ETCHER	Lam Research	SEZ203	200	2005
7490	DICING	UV IRRADIATION SYSTEM	LINTEC	RAD-2000M/6	150	2005
7513	DICING	UV IRRADIATION SYSTEM	LINTEC	RAD-2000m/8	200	2006
7512	MOUNTING	WAFER MOUNTER	LINTEC	RAD-2500m/8	200	2007
7389	METROLOGY	FILM THICKNESS MEASUREMENT	Nanometrics	NanoSpec6100	200	1998
8245	METROLOGY	FILM THICKNESS MEASUREMENT	Nanometrics	NanoSpec9200	200	2001
7338	METROLOGY	FILM THICKNESS MEASUREMENT	Nanometrics	NanoSpec9310	200/300	2008
7660	PHOTOLITHO	STEPPER_i-Line	Nikon	NSR2005i10C	150	1994
7335	PHOTOLITHO	STEPPER_KrF	Nikon	NSR-2205EX14C	200	1998
7334	PHOTOLITHO	STEPPER_KrF	Nikon	NSR-2205EX14C	200	1999
7430	PHOTOLITHO	STEPPER_i-Line	Nikon	NSR-4425i	125	1997
7112	CVD	EPITAXIAL DEPOSITION	NuFlare Technology	HT2000B	150	2007
7432	CMP	CMP	Okamoto	SPP-600S GRIND	125	1998
7568	WET	SUPERCritical RINSER&DRYER	Rexxam	SCRD6	150	2008
7239	METROLOGY	FILM THICKNESS MEASUREMENT	Rudolph	S200ETCH	200	2000
7263	WET	POST CMP CLEANING SYSTEM	SCREEN	AS2000	200	1998
8391	WET	POST CMP CLEANING SYSTEM	SCREEN	AS2000	200	1998
7622	WET	POST CMP CLEANING SYSTEM	SCREEN	AS2000	200	2000
7472	RTP	RTA	SCREEN	LA-830	200	-
7208	PHOTOLITHO	COATER	SCREEN	SK-80BW-AVQ	200	1998
7209	WET	WAFER SCRUBBER	SCREEN	SS-W80A-AR	200	1995
6851	WET	WAFER SCRUBBER	SCREEN	SS-W80A-AR	200	2000
7211	WET	WAFER SCRUBBER	SCREEN	SS-W80A-AVR	200	1998
6914	WET	WAFER SCRUBBER	SCREEN	SS-W80A-AVR	200	2002
7425	METROLOGY	FILM THICKNESS MEASUREMENT	SOPRA	GESP5	200	2010
7869	CVD	MO CVD	TAIYO NIPPON SAN SO	SR64212HKS	150	2010
7495	METROLOGY	AUTOMATIC VISUAL INSPECTION	TAKANO (TOPCON)	Vi-4202	200	2004
6875	METROLOGY	WAFER PARTICLE COUNTER	TAKANO (TOPCON)	WM-5000	300	2005
7467	BACK GRIND	TAPE REMOVER	Takatori	AMR-2200G	200	-

Tool Code	PROCESS	EQUIPMENT	MANUFACTURER	MODEL	WAFER SIZE	VINTAGE
7244	PHOTOLITHO	COATER&DEVELOPER	TEL	ACT8(2C2D)	200	1998
7860	DIFFUSION	DIFFUSION	TEL	Alpha-8SE	200	2005
7288	FURNACE	FURNACE_LP-CVD	TEL	IW-6C	150	1994
6917	WET	CLEANING SYSTEM	TEL	MARK-7	200	1993
7810	PHOTOLITHO	COATER	TEL	MARK-8	150	1999
8464	PHOTOLITHO	COATER&DEVELOPER	TEL	MARK-V	200	1992
7431	PHOTOLITHO	COATER&DEVELOPER	TEL	MARK-Vz	150	1998
7762	TEST	WAFER PROBER	TEL	P-12XL	300	2002
7763	TEST	WAFER PROBER	TEL	P-12XL	300	2002
7717	TEST	WAFER PROBER	TEL	P-12XLn	300	2006
7761	TEST	WAFER PROBER	TEL	P-8XL	200	2000
7757	TEST	WAFER PROBER	TEL	P-8XL	200	2004
7729	TEST	WAFER PROBER	TEL	P-8XL	200	2008
8270	WET	WAFER SCRUBBER	TEL	SS-4	200	2001
8271	WET	WAFER SCRUBBER	TEL	SS-4	200	2003
7715	ETCH	PLASMA ETCHER	TEL	TACTRAS	300	2013
8440	ETCH	OXIDE ETCHER	TEL	TE5000ATC	150	1992
7827	ETCH	OXIDE ETCHER	TEL	TE8500(S)	150	2000
7398	ETCH	OXIDE ETCHER	TEL	TE8500(S)ATC	150	1992
8441	ETCH	OXIDE ETCHER	TEL	TE8500(S)ATC	150	1993
8248	ETCH	OXIDE ETCHER	TEL	TE8500(S)ATC	200	1995
7252	ETCH	OXIDE ETCHER	TEL	TE8500ATC	200	1995
7714	ETCH	OXIDE ETCHER	TEL	Telius SCCM	300	2000
7571	ETCH	OXIDE ETCHER	TEL	Unity Me 85D	200	2003
7339	ETCH	OXIDE ETCHER	TEL	UnityII-855II	200	1996
7248	ETCH	OXIDE ETCHER	TEL	UnityII-855II	200	1996
8306	ETCH	OXIDE ETCHER	TEL	UnityIIe-655II	200	2002
8302	ETCH	OXIDE ETCHER	TEL	UnityIIe-855II	200	1997
8341	ETCH	OXIDE ETCHER	TEL	UnityIIe-855II	200	2002
8304	ETCH	OXIDE ETCHER	TEL	UnityIIe-855SS	200	2000
7853	ETCH	OXIDE ETCHER	TEL	UnityIIe-855SS	200	2006
8061	ASHER	ASHER	TOK	TCA-3822	200	1995
7408	ASHER	ASHER	TOK	TCA-3822	200	1995
8352	ETCH	OXIDE ETCHER	TOK	TCE-3822	200	-
8351	ETCH	OXIDE ETCHER	TOK	TCE-3822	200	-
7644	METROLOGY	AUTOMATIC VISUAL INSPECTION	TORAY	INSPECTRA-3000TR200M	90/150/200	2015
8443	PHOTOLITHO	STEPPER_i-Line	ULTRATECH	Saturn-SS3	150	2001
7475	PVD	EVAPORATOR_E GUN	ULVAC	ei-7L	200	-
7619	PHOTOLITHO	WAFER EDGE EXPOSURE	Ushio	PE-250R2HK	200	-
7620	PHOTOLITHO	WAFER EDGE EXPOSURE	Ushio	PE-250T2HM	200	-
7581	PHOTOLITHO	UV CURING SYSTEM	Ushio	UMA-1002-HC933HD	200	1998

Industrial Machinery Business Department No.2

Corporate Business Department

Business Management Division

**Mitsubishi HC Capital Inc.**

3-1, Nishi-shimbashi, 1-chome, Minato-ku, Tokyo 105-0003, Japan

<https://www.mitsubishi-hc-capital.com/english/hc/semicon/>